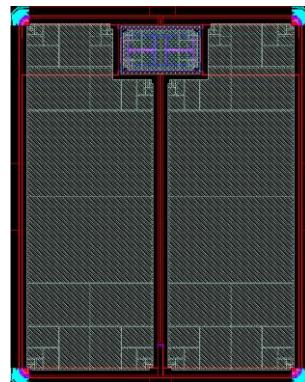


### Description

Silicon Carbide (SiC) MOSFET use a completely new technology that provide superior switching performance and higher reliability compared to Silicon. In addition, the low ON resistance and compact chip size ensure low capacitance and gate charge. Consequently, system benefits include highest efficiency, faster operating frequency, increased power density, reduced EMI, and reduced system size.

### Features

- High Speed Switching with Low Capacitances
- High Blocking Voltage with Low RDS(on)
- Simple to drive with Standard Gate Drive
- 100% avalanche tested
- Maximum junction temperature of 175°C
- ROHS Compliant



### Application

- EV Charging
- DC-AC Inverters
- High Voltage DC/DC Converters
- Switch Mode Power Supplies
- Power Factor Correction Modules
- Motor Drives

Part Number	Die Size
AMG100N1700MB	5.179 × 5.179

### Absolute Maximum Ratings( $T_c=25^\circ\text{C}$ )

Symbol	Parameter	Value	Unit
$V_{DS}$	Drain-Source Voltage	1700	V
$I_D$	Drain Current(continuous)at $T_c=25^\circ\text{C}$	100	A
$I_{DM}$	Drain Current (pulsed)	238	A
$V_{GS}$	Gate-Source Voltage	-8/+19	V
$T_J, T_{Stg}$	Junction and Storage Temperature Range	-55 to +175	°C



**AMG100N1700MB**

**Electrical Characteristics( $T_J = 25^\circ\text{C}$  unless otherwise specified)**

**Typical Performance-Static**

Symbol	Parameter	Test Conditions	Min.	Typ.	Max.	Unit
$\text{BV}_{\text{DSS}}$	Drain-source Breakdown Voltage	$I_D=250\mu\text{A}, V_{GS}=0\text{V}$	1700			V
$I_{\text{DSS}}$	Zero Gate Voltage Drain Current	$V_{DS}=1700\text{V}, V_{GS}=0\text{V}, T_J=25^\circ\text{C}$			100	$\mu\text{A}$
$I_{GSS+}$	Gate-body Leakage Current	$V_{GS}=19\text{V}, V_{DS}=0\text{V}$			100	nA
$I_{GSS-}$	Gate-body Leakage Current	$V_{GS}=-8\text{V}, V_{DS}=0\text{V}$			100	nA
$V_{GS(\text{th})}$	Gate Threshold Voltage	$V_{DS}=V_{GS}, I_D=25\text{mA}$	1.8	3	4	V
$R_{DS(\text{on})}$	Static Drain-source On Resistance	$V_{GS}=15\text{V}, I_D=75\text{A}$		22	29	$\text{m}\Omega$
$R_G$	Gate Resistance	$V_{GS}=0\text{V}, f=1\text{MHz}$		3		$\Omega$

**Typical Performance-Dynamic**

$C_{iss}$	Input Capacitance	$V_{DS}=1200\text{V}, f=1000\text{KHz}, V_{GS}=0\text{V}$		6500		pF
$C_{oss}$	Output Capacitance			195		pF
$C_{rss}$	Reverse Transfer Capacitance			16		pF
$Q_g$	Total Gate Charge	$V_{DS}=1200\text{V}, I_D=50\text{A}, V_{GS}=-4\text{~}15\text{V}$		255		nC
$Q_{gs}$	Gate-source Charge			73		nC
$Q_{gd}$	Gate-Drain Charge			62		nC
$t_{d(on)}$	Turn-on Delay Time	$V_{DD}=1200\text{V}, I_D=50\text{A}, V_{GS}=-4\text{~}15\text{V}, R_G=0\Omega,$		181		ns
$t_r$	Rise Time			29		ns
$t_{d(off)}$	Turn-off Delay Time			85		ns
$t_f$	Fall Time			25		ns

**Typical Performance-Reverse Diode**

Symbol	Parameter	Test Conditions	Min.	Typ.	Max.	Unit
$V_{FSD}$	Forward Voltage	$V_{GS}=0\text{V}, I_F=37.5\text{A}, T_J=25^\circ\text{C}$	3		6	V
		$V_{GS}=0\text{V}, I_F=37.5\text{A}, T_J=150^\circ\text{C}$	3		6	V
$t_{rr}$	Reverse Recovery Time	$V_{GS}=0\text{ V}, I_F=30\text{ A}, V_R=1200\text{ V}, di/dt= 100\text{ A}/\mu\text{s}$		99		ns
$Q_{rr}$	Reverse Recovery Charge			810		nC
$I_{rrm}$	Peak Reverse Recovery Current			21		A

**Mechanical Parameters**

Parameter	Typical Value	Unit
Die Dimensions (L×W) without scribe line	$5.099 \times 5.099$	mm
Gate Pad Dimensions (L×W)	$1.19 \times 0.598$	mm
Source Pad Metal Dimensions (LxW)	$4.480 \times 4.480$	mm
Scribe Line	80	um
Die Thickness	$175 \pm 25$	um
Top Side Source metallization (Al)	4	um
Top Side Gate metallization (Al)	4	um
Bottom Drain metallization (Ti/Ni/Ag)	0.2/0.3/2	um

**Chip Dimensions**

